

**REMARKS**

Applicants wish to thank Examiner Dentz for indicating allowability of Claim 5 if rewritten in independent form including all of the limitations of the base claim and any intervening claims. Claim 5 has been rewritten in independent form and thus should be allowed.

Applicants respectfully request reconsideration of the application, as amended, in view of the following remarks.

Namiki et al (JP 2000131848), Matsuno et al, JP 53-44539 and Herrin et al (US 4,052,439) fail to disclose or suggest the halogenoacetoxyadamantane derivatives of Claims 3, 4 and 5 and the process for producing the halogenoacetoxyadamantane derivatives of Claim 6.

Namiki et al, Matsuno et al, JP 53-44539 and Herrin et al neither disclose nor suggest “1-halogenoacetoxyperfluoroadamantane” as claimed in Claim 3 and “2-alkyl-2-halogenoacetoxyadamantane” as claimed in Claim 4 of the present invention.

Further, none of Namiki et al, Matsuno et al, JP 53-44539 and Herrin et al disclose or suggest a photoresist composition or a dry-etching resistance improving agent as claimed in Claims 8-13, respectively.

Regarding Claim 6, there is no disclosure or suggestion in Namiki et al, Matsuno et al, JP 53-44539 and Herrin et al of a process for producing a halogenoacetoxyadamantane derivative, comprising:

reacting a hydroxyl group of an adamantane skeleton directly with halogenoacetic halide or reacting said hydroxyl group with a lithiation agent to obtain a lithiumoxy group and then reacting halogenoacetic halide therewith to introduce a halogenoacetoxy group;

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wherein said halogenoacetoxyadamantane derivative is 2-alkyl-2-halogenoacetoxyadamantane, 1-halogenoacetoxy-3-hydroxyadamantane or 1-halogenoacetoxyperfluoroadamantane.

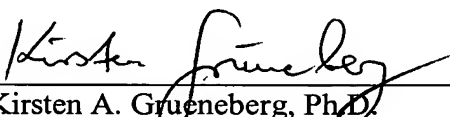
Therefore, the rejections over Namiki et al (JP 2000131848), Matsuno et al, JP 53-44539 and Herrin et al (US 4,052,439) are believed to be unsustainable as the present invention is neither anticipated nor obvious and withdrawal of these rejections is respectfully requested.

This application presents allowable subject matter, and the Examiner is kindly requested to pass it to issue. Should the Examiner have any questions regarding the claims or otherwise wish to discuss this case, he is kindly invited to contact Applicants' below-signed representative, who would be happy to provide any assistance deemed necessary in speeding this application to allowance.

Respectfully submitted,

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